

PTW ASIA PTE LTD

ectron Ltd. Expedius+ Wafer Processing
Tokyo Electron Ltd.
Expedius+
Batch Wafer Processing
2007
W083557
300mm
Pre Diffusion Clean

Bath-1: SPM

Operating: 110 - 150°C, H2SO4/H2O2 (3:1), circulation

Chemical spiking: auto concentration feedback

Bath Material: Quartz

Bath-2: QDR (hot)

Operating: DIW rinse (75°C, 40 – 80 L/min)

Bath Material: PTFE

Megasonic: 950 kHz, 2400W (600*4)

Bath-3: APM

Operating: 35 - 85°C, NH4OH/H2O2/DIW (1:1:15), 15 L/min, circulation

Chemical spiking: auto concentration feedback

Bath Material: PTFE

Megasonic: 950 kHz, 2400W (600*4)

Bath-4: POU

Operating: 70°C, NH4OH/H2O2

DIW Shower (hot / cold)
Bath Material: PTFE

Megasonic: 950 kHz, 2400W (600*4)

Bath-5: HPM

Operating: 35 - 80°C, HCL/H2O2/DIW (1:1:5)

Bath Material: Quartz

Bath-6: QDR (hot)

Operating: DIW rinse (75°C, 40 – 80 L/min)

Bath Material: PTFE

Megasonic: 950 kHz, 2400W (600*4)

Dryer: SD2

Operating: 49% DHF (1:200), IPA/N2 200°C, 100 L/min

Resistivity monitoring (Horiba)

Bath Material: PTFE

Damaged / Missing parts:

IPA Detect Sensor damage SPM Bath damage









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All Equipment is offered subject to prior sale. This item will be quoted based upon specific terms and configuration required. Interested parties may contact PTW Asia Pte Ltd at:

ask@ptwsingapore.com

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